

ABSTRACT OF THE DISCLOSURE

[0061]An apparatus and method for supplying cesium that can readily control the amount of supplied cesium gas and continuously supply the cesium gas for a long period of time are disclosed in the present invention. The apparatus for supplying cesium includes a gas flow controller controlling an amount of an externally introduced inert gas, a pre-heater pre-heating the inert gas introduced through a first gas flow tube from the gas flow controller, a cesium vaporizer emitting a cesium gas from a cesium containing source to a third gas flow tube by using the inert gas introduced through a second gas flow tube from the pre-heater, and a pressure detector detecting a vapor pressure of the cesium vaporizer. It is emphasized that this abstract is provided to comply with the rules requiring an abstract that will allow a searcher or other reader to quickly ascertain the subject matter of the technical disclosure. It is submitted with the understanding that it will not be used to interpret or limit the scope or meaning of the claims.